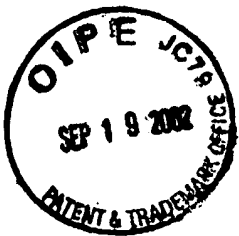


INFORMATION DISCLOSURE CITATION IN AN APPLICATION



(PTO-1449)

 ATTY. DOCKET NO.
5917/FET/FET/DV

 SERIAL NO.
09/998,372

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3700 MAIL ROOM

 APPLICANT
Young Joseph PAIK

 FILING DATE
November 30, 2001

 GROUP
3723

U.S. PATENT DOCUMENTS

EXAMINER'S INITIALS	PATENT NO.	DATE	NAME	CLASS	SUBCLASS	FILING DATE
BA	4,698,766	10/06/87	Entwistle et al.	1	1	05/17/85
	4,967,381	10/30/90	Lane et al.	1	1	07/06/89
	5,208,765	05/04/93	Turnbull	1	1	07/20/90
	5,226,118	07/06/93	Baker et al.	1	1	01/29/91
	5,231,585	07/27/93	Kobayashi et al.	1	1	06/20/90
	5,420,796	05/30/95	Weling et al.	1	1	12/23/93
	5,469,361	11/21/95	Moyne	1	1	06/06/94
	5,525,808	06/11/96	Irie et al.	1	1	12/20/94
	5,586,039	12/17/96	Hirsch et al.	1	1	02/27/95
	5,603,707	02/18/97	Trombetta et al.	1	1	11/28/95
	5,664,987	09/09/97	Renteln	1	1	09/04/96
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BA	5,832,224	11/03/98	Fehskens et al.	1	1	06/14/96



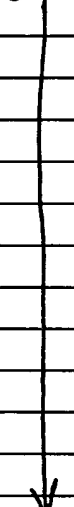







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EXAMINER'S INITIALS	PATENT NO.	DATE	COUNTRY	CLASS	SUBCLASS	Translation	
						Yes	No
BA	61-171147	08/01/86	Japan	1	1		X
	6-184434	07/05/94	Japan	1	1		X
	0 621 522 A2	10/26/94	Europe	1	1	X	
	8-50161	02/20/96	Japan	1	1		X
BA	8-304023	11/22/96	Japan	1	1		X

OTHER ART (Including Author, Title, Date, Pertinent Pages, Etc.)

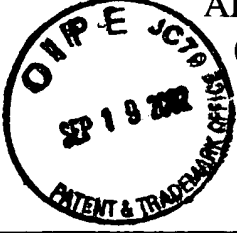

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INFORMATION DISCLOSURE CITATION IN AN APPLICATION  (PTO-1449)				ATTY. DOCKET NO. 5917/FET/FET/DV		SERIAL NO. 09/998,372	
				APPLICANT Young Joseph PAIK			
				FILING DATE November 30, 2001		GROUP 3723	
U.S. PATENT DOCUMENTS							
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  	5,859,964	01/12/99	Wang et al.			10/25/96	
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						Yes	No
  	0 747 795 A2	12/11/96	Europe			X	
	10-173029	06/26/98	Japan				X
	0 895 145 A1	02/03/99	Europe			X	
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	Schmid, Hans Albrecht. 1995. "Creating the Architecture of a Manufacturing Framework by Design Patterns." Austin, Texas: OOPSLA.						
	Baliga, John. July 1999. "Advanced Process Control: Soon to be a Must." Cahners Semiconductor International. www.semiconductor.net/semiconductor/issues/issues/1999/jul99/docs/feature1.asp						
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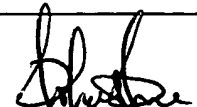
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				APPLICANT Young Joseph PAIK			
				FILING DATE November 30, 2001		GROUP 3723	
U.S. PATENT DOCUMENTS							
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SA	6,178,390	01/23/01	Jun	—	—	09/08/98	
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SA	6,240,330	05/29/01	Kurtzberg et al.	—	—	05/28/97	
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SA	WO 00/05759	02/03/00	WO	—	—	X	
SA	WO 00/35063	06/15/00	WO	—	—	X	
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SA	July 5, 2001. "Motorola and Advanced Micro Devices Buy ObjectSpace Catalyst Advanced Process Control Product for Five Wafer Fabs." Semiconductor FABTECH. www.semiconductorfabtech.com/industry.news/9907/20.07.shtml						
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SA	Johnson, Bob. June 10, 2002. "Advanced Process Control Key to Moore's Law." Gartner, Inc.						
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INFORMATION DISCLOSURE CITATION IN AN APPLICATION (PTO-1449)				ATTY. DOCKET NO. 5917/FET/FET/DV		SERIAL NO. 09/998,372	
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	6,252,412	06/26/01	Talbot et al.	—	—	01/08/99	
	6,263,255	07/17/01	Tan et al.	—	—	05/18/98	
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	6,298,274	10/02/01	Inoue	—	—	09/01/99	
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V	6,345,315	02/05/02	Mishra	—	—	08/12/98	
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V	2001-76982	03/23/01	Japan	—	—		X
BR	WO 01/33501 A1	05/10/01	WO	—	—	X	
OTHER ART (Including Author, Title, Date, Pertinent Pages, Etc.)							
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